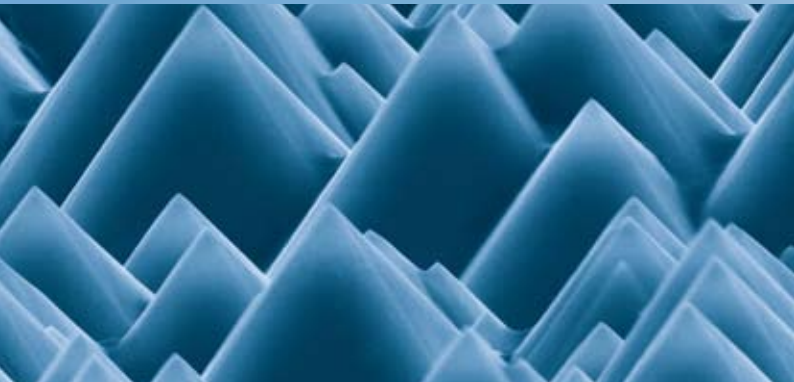


SOLAR

monoTEX[®]

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monoTEX[®]

IPA free alkaline texturing for mono Si-wafers

monoTEX[®] is a new type of moderating and wetting agent for alkaline texturing. The common agent IPA is very tricky to use since process temperature and boiling point are in the same temperature range. RENA monoTEX[®] is operating at temperatures far below the boiling point of its components and behaves almost "linear" towards temperature and alkali concentration changes.

Areas of application

- Texturing of monocrystalline Si-wafers
- KOH based chemistry
- Batch application in RENA BatchTex

Features and benefits

- | | |
|---|---|
| <ul style="list-style-type: none"> • IPA free • Production proven by processing > 200 million wafers • Process temperature below boiling points • No VOC and no handling of EX-risk liquid • Large process window • Process time <ul style="list-style-type: none"> • < 20 min guaranteed employing RENA's pre-cleaning • Typically 15 min | <ul style="list-style-type: none"> • Uniform pyramids (2 - 5 μm) • Average reflectance < 12.5% within 400 - 1100 nm • Linear behaviour towards parameter changes • Cost saving usage • Bath lifetime of > 30 runs with RENA's pre-clean • Safe handling by quick exhaust of hydrogen • Environmental-friendly by low organic load in waste liquid, biodegradable |
|---|---|





BatchTex
handling

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Front view BatchTex

monoTEX[®]

Technical Data monoTEX[®]

Basic recipe	1.7 wt % KOH, 1.5 wt % monoTEX [®]
Organic components	< 0.05 % in the etching solution
Typical process temperature	80°C
Process time	< 20 min guaranteed, after RENA conditioning pre-cleaning typically around 15 min